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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHO ET AL.

Atty. Ref.: 4105-73; Confirmation No. 6675

Appl. No. 10/568,770

TC/A.U. 1765

Filed: February 21, 2006

Examiner: Unknown

For: FERROELECTRIC THIN-FILM PRODUCTION METHOD, VOLTAGE-APPLICATION
ETCHING APPARATUS, FERROELECTRIC CRYSTAL THIN-FILM SUBSTRATE,
AND FERROELECTRIC CRYSTAL WAFER

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May 7, 2007

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESPONSE TO NOTICE OF NON-COMPLIANT AMENDMENT

Responsive to the Notice of Non-Compliant Amendment dated May 2, 2007, attached is
a revised set of claims correcting the errors in claim 21 pointed out in the Notice.

An early and favorable action on the merits is awaited.

Respectfully submitted,

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By: _____

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